

Amended claim 26 recites, among other things, the recitations of "obtaining data regarding **an environment in one of an exposure chamber** in which said exposure apparatus is contained and a processing chamber in which said substrate processing apparatus is contained;" and "controlling the environment in the other of the exposure chamber and the processing chamber on the basis of the obtained data."

Amended claim 27 recites, among other things, the recitations of "an adjusting device connected to said exposure chamber and which **adjusts an environment in said exposure chamber**; and "a control device electrically connected to said adjusting device and which controls said adjusting device on the basis of data regarding the environment in said processing chamber."

Amended claim 28 recites, among other things, the recitations of "an adjusting device connected to said processing chamber and which **adjusts an environment in said processing chamber**;" and "a control device electrically connected to said adjusting device and which controls said adjusting device on the basis of data regarding environment in said exposure chamber."

Thus, these claims also patentably distinguish over Hasegawa et al. Claims 2, 3, 6-10, 13-19, 21, 22, 24 and 25 all, directly or indirectly, depend from one of these independent claims.

#### **Rejections under 35 USC §103(a)**

Claims 4, 11 and 29 were rejected under 35 USC §103 (a) as being anticipated by Hasegawa et al (USP No. 5,828,572).

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These claims depend from claims which patentably distinguish over Hasegawa et al as discussed above.

If, for any reason, it is felt that this application is not now in condition for allowance, the Examiner is requested to contact Applicant's undersigned attorney at the telephone number indicated below to arrange for an interview to expedite the disposition of this case.

In the event that this paper is not timely filed, Applicant respectfully petitions for an appropriate extension of time. The fees for such an extension or any other fees which may be due with respect to this paper, may be charged to Deposit Account No. 01-2340.

Respectfully submitted,

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controlling the environment in the other [apparatus] chamber of the exposure chamber and the processing chamber on the basis of the obtained data.

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27. (Amended) An exposure apparatus [adapted to expose] which exposes a substrate and which is connected to a substrate processing apparatus contained in a processing chamber which processes the substrate before or after exposure of the substrate, the exposure apparatus comprising:

[a] an exposure chamber [disposed around an exposure body system which exposes the substrate] which is separate from the processing chamber and contains the exposure apparatus;

an adjusting device connected to said exposure chamber and [adapted to adjust] which adjusts an environment in said exposure chamber; and

a control device electrically connected to said adjusting device and [adapted to control] which controls said adjusting device on the basis of data regarding the environment in said [substrate processing apparatus] processing chamber.

28. (Amended) A substrate processing apparatus [adapted to process] which processes a substrate and which is connected to an exposure apparatus contained in an exposure chamber which exposes the substrate before or after the substrate processing, the substrate processing apparatus comprising:

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a processing chamber [disposed around a substrate processing body system which processes the substrate] which is separate from the exposure chamber and contains the substrate processing

apparatus;

an adjusting device connected to said processing chamber and [adapted to adjust] which adjusts an environment in said processing chamber; and

a control device electrically connected to said adjusting device and [adapted to control] which controls said adjusting device on the basis of data regarding environment in said exposure [apparatus] chamber.

#### REMARKS

Claims 1-8, 10-15, 17, and 19-29 are pending in this application after the entry of this amendment.

In the prosecution of the parent application, Serial No. 09/350,923, which has been abandoned, claims 1-29 were rejected. Since claims 1-29 of the present application respectively correspond to the claims 1-29 of the parent application, the following remarks address the Office Action of the parent application dated May 9, 2000. Reconsideration of the rejections in view of these amendments and the following remarks is respectfully requested.

**Rejections under 35 USC §102**

Claims 1-3, 5-10, and 12-28 were rejected under 35 USC §102 (e) as being anticipated by Hasegawa et al (USP No. 5,828,572).

Amended claim 1 recites, among others, the recitations of "an environment sensor provided in **at least one of the first and the second chambers** which measures an environment in said at least one of the first and the second chambers" and "a control device, which is electrically connected to the environment sensor, and which **controls the environment in said at least one of the first and the second chambers.**"

Hasegawa et al appears to disclose: (1) a first chamber 3 having an exposure apparatus and a second chamber 4 having a coater 41 and a developer 42; (2) temperature sensors 9a to 9c at plurality of sites in a plant 1; and (3) adjustment of a condition in the production plant 1 according to the results measured by temperature sensors 9a to 9c and/or an operating condition of each of processing apparatuses (i.e., an exposure apparatus, coater and a developer).

In Hasegawa et al, however, the sensors do not monitor an environment in a chamber 3 or an environment in a chamber 4. While the temperature sensors 9a to 9c disclosed in Hasegawa et al are disposed inside the production plant 1 as shown in Fig. 1, they are not disposed in the chamber 3 or chamber 4. Therefore, a condition of an environment in each of the chambers themselves cannot be measured by the temperature sensors 9a to 9c.

Although Hasegawa et al discloses adjusting a condition of an environment in the plant 1, what can be adjusted in Hasegawa et al is limited to an adjustment of a condition outside the

chambers 3 and 4. Thus, Hasegawa et al fails to disclose a method of controlling a condition of an environment inside the chambers 3 and 4.

The Office Action alleged, at lines 6-8 on page 6, that "Reference numeral 11 denotes a main controller for controlling the entire air conditioning system in the plant 1 by monitoring the operating stage of the exposure chamber 3 (see col.3, lines 15-17)." However, the description in col. 3, lines 15-17 of Hasegawa et al merely shows controlling the blowing capability of each of FFUs (fan filter units) 7a-7e and the cooling capability of each of cooling coils 8a-8e, based on an operating condition of an exposure apparatus and the results measured by sensors 9. Namely, during the operation of the exposure apparatus, FFUs 7 and the cooling coils 8, which can adjust an environment surrounding the chamber 3, are adjusted so that the capability of the FFU 7 and the cooling coils 8 is improved. However, both the FFUs 7 and the cooling coils 8 aim to adjust a local region (i.e., outside of the chambers 3 and 4), but do not adjust an environment inside of the chambers 3 and 4.

Incidentally, it should be pointed out that the examiner's opinion reading "monitoring the operating stage of the exposure chamber 3" should be corrected to "monitoring the operating state of the exposure chamber 3," in view of the description of col. 3, lines 15-17.

In addition, the Office Action also alleged, at lines 8 to 10 on page 6, that "Hasegawa et al further suggest in column 4, lines 64-66 that 'it is possible to perform and concentrate high-level air-conditioning control at a particular location and at a request time.'" However, Hasegawa et al only disclose controlling a condition of the environment inside the plant 1 as mentioned